App No.: New U.S. Appln. Docket No.: 543822005500

Inventor: Dirk EFFERENN et al.

Title: METHOD FOR MASKING A RECESS IN A STRUCTURE HAVNG A HIGH ASPECT RATIO Sheet 1 of 2

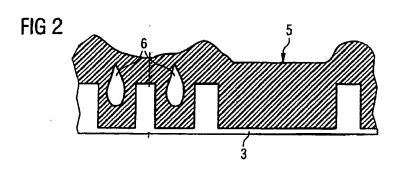
FIG 1

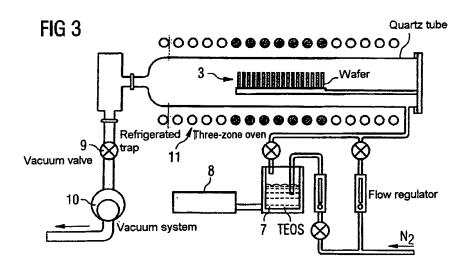
4/4a

High AR

Low AR

4/4d





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